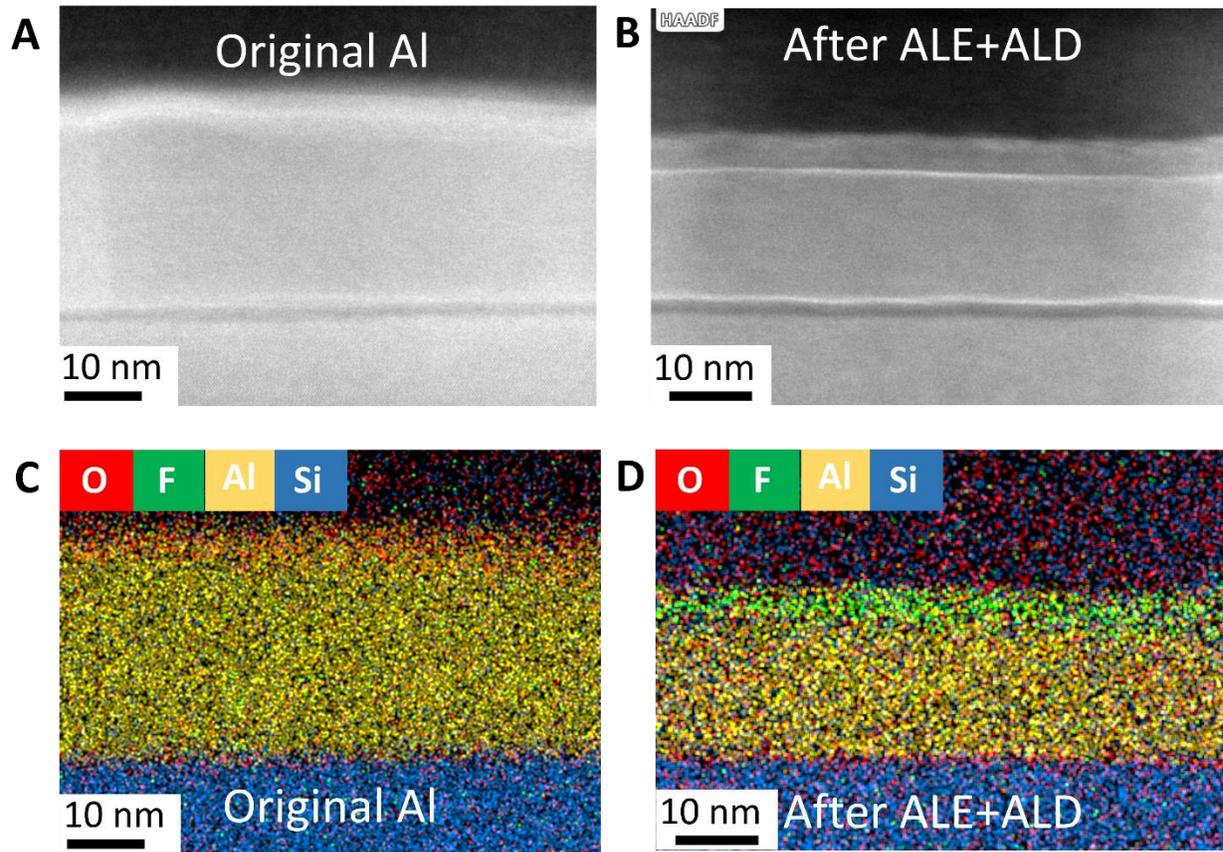


The supplementary Figure of Isotropic plasma-thermal atomic layer etching and in-situ atomic layer deposition passivation of aluminum films for superconducting circuits



Supplementary Figure. Al thin film characterization before and after atomic layer etching (ALE). (a)-(b) Cross-sectional TEM images: (a) before and (b) after ALE. (c)-(d) Selective area EDS: (c) before and (d) after ALE.